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REMARKS

Claims 1-4, 7, 12 and 21 are pending. Claims 5, 6 and 9-11 have been

cancelled and Claims 8 and 13-20 have been withdrawn from consideration. Claim 1 has

been amended. Support for the amendment can be found on page 6, line 12 of the

specification. No new matter is added. Favorable consideration of the currently pending

claims is respectfully requested in light of the foregoing amendments and following remarks.

Rejections Under 35 U.S.C. §103:

In the Office Action, the Examiner rejected Claims 1-4, 7, 12 and 21 under 35

U.S.C. § 103(a) as unpatentable over Connell et al. (UK 1,037,144) in view of Timmons et

al. (5,876,753) or vice versa. In addition, the Examiner rejected Claims 1-4, 7, 12 and 21

under 35 U.S.C. § 103(a) as unpatentable over Timmons et al. in view of Kolluri et al.

(5.723,219). Applicants respectfully submit that the amendments to the claims overcome the

Examiner's rejection.

Applicants have amended claim 1 to recite the preferred average power

density of less than 0.0025 W/cm³, as described on page 6, line 12 of the specification. The

examples described in the specification also fall within this limitation. None of the

documents cited by the Examiner disclose or suggest an average power density below 0.0025

 W/cm^3 .

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Applicants submit that a person skilled in the art would not combine the

teachings of Timmons et al. and either Connell et al. or Kolluri et al. to achieve the presently

claimed method, because the chemistry of the monomers used by Timmons et al. is different

to that disclosed by Connell et al. and Kolluri et al.. Furthermore, Timmons et al. fail to

define "low power", nor does they provide a value for power density or chamber volume.

Applicants submit that the limitations of Claim 1 fall well outside the range of conditions

taught by Timmons et al. Therefore, even if the materials of Connell et al. or Kolluri et al.

were subjected to the pulsing conditions disclosed by Timmons et al., the limitations of

Claim 1 would not be satisfied.

The process of plasma polymerization requires the careful choice of monomer

and plasma conditions to provide a method where organic polymers can be deposited, as a

thin-film, onto a variety of substrates. Prior to the work of the applicants, it was believed

that plasma chemists/physicists relied mostly on "low" (this being a relative term) powers,

either continuous or pulsed, to retain monomer functionalities. However, the effect of

plasma pulsing on free radical initiated polymerization has not been well understood.

Applicants used monomers that are susceptible to free radical initiated polymerization (e.g.,

an acrylate or methacrylate). These monomers possess an unsaturated (C=C) group that will

react with a radical (R') to produce RC-C'. This new radical can then add to another

unsaturated group to produce a 'growing' polymer chain that can further add to another

unsaturated monomer. Although the solution chemistry of acrylates and methacrylates is

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extensively documented in the literature, the plasma chemist (such as Timmons) has

generally ignored these types of monomers. Applicants have found that a very short, low

power pulse initiates such monomers and that growth of the polymer occurs during a

relatively long off period. Thus a high frequency pulse and short on time, resulting in much

lower average power densities, is beneficial for the deposition of polymers, which rely

substantially on free radical initiated polymerization.

As stated previously, the patent of Timmons et al. broadly relates to the

deposition of "carbonaceous compounds having a reactive functional group." This is

considered to be an excessively broad and speculative scope, bearing in mind that the nature

of the monomer is known to affect the success of deposition (column 7, line 36-37).

Timmons et al. focus on allyl-type compounds and although they state that the technology

can be "extended to non-allyl precursors" the person skilled in the art could only

meaningfully interpret this to mean "related monomers" or other precursors that might be

expected to react in a similar way. Allyl type monomers are not particularly susceptible to

free radical initiated polymerization:

polymerization of allyl ester, ethers, amines and related monomers. The allylic hydrogens of these monomers are activated towards abstraction by both the double bond and the heteroatom substituent and cause

"Transfer to monomer is of particular importance during the

by both the double bond and the heteroatom substituent . . . and cause the allyl monomers to retard polymerization." Allyl monomers, THE

CHEMISTRY OF FREE RADICAL POLYMERIZATION, G. Moad and D.

Solomon, ISBN 0 08 042078 8, 1995 Pergamon.

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Therefore, the chemistry occurring in the Timmons et al. plasma reactor is

different from that occurring in the claimed method. For this reason the presently claimed

selection of a combination of materials and average power densities not specifically

disclosed in Timmons et al. is considered to be a purposeful selection.

Moreover, Connell et al. relates to a continuous wave deposition process. This

clearly fails to facilitate free radical initiated polymerisation in the way envisaged by the

claimed method. Applicants would expect the process of Connell et al. to result in a

deposited polymer having a very different structure from that produced by the claimed

process. In particular, applicants would expect it to have a significantly higher degree of

cross-linking.

In addition, Kolluri et al. is directed to functional film networks comprising a

number of plasma deposited layers which maximize the functional density of the film.

Kolluri et al. provides insufficient disclosure as to how the pulsing conditions might affect

the quality and functional density of any particular layer. The present invention improves on

Kolluri et al. by further reducing the average power density. Applicants would expect the

conditions described and claimed in the present application to reduce layer fragmentation and

to increase functionality of the deposited layer.

Accordingly, applicants request that the rejection of Claims 1-4, 7, 12 and 21

under 35 U.S.C. § 103(a) over Connell et al. in view of Timmons et al. or vice versa be

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withdrawn. Applicants also request that the rejection of Claims 1-4, 7, 12 and 21 under 35

U.S.C. § 103(a) over Timmons et al. in view of Kolluri et al. be withdrawn.

CONCLUSION

Based upon the amendments and remarks provided above, applicants believe

that Claims 1-4, 7, 12 and 21 are in condition for allowance. A Notice of Allowance is

therefore respectfully solicited.

No additional fees are believed due; however, the Commissioner is hereby

authorized to charge any additional fees that may be required, or credit any overpayment, to

Deposit Account No. 11-0855.

If the Examiner believes any informalities remain in the application that may

be corrected by Examiner's Amendment, or there are any other issues that can be resolved by

telephone interview, a telephone call to the undersigned attorney at (404) 815-6500 is

respectfully solicited.

Respectfully submitted,

Jamie L. Greene

Reg. No. 32,467

KILPATRICK STOCKTON LLP

1100 Peachtree Road, N.E.

Suite 2800

Atlanta, Georgia 30309-4530

Telephone: (404) 815-6500

Attorney Docket No. 41577/266144 (P1242)